

Modeling of surfaces: the third dimension in XPS analysis of multilayer structures

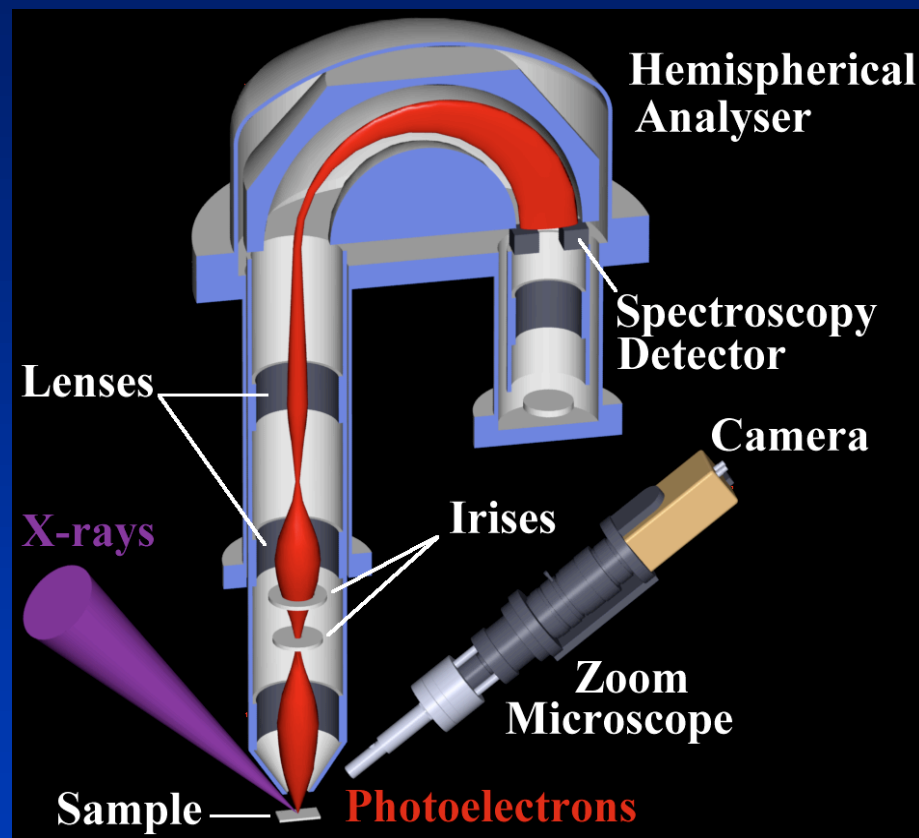
Antonella Rossi

Universita' degli Studi di Cagliari (Italy)
and Laboratory for Surface Science and Technology
Department of Materials
Swiss Federal Institute of Technology (ETH)
Zürich, Switzerland



XPS Analysis

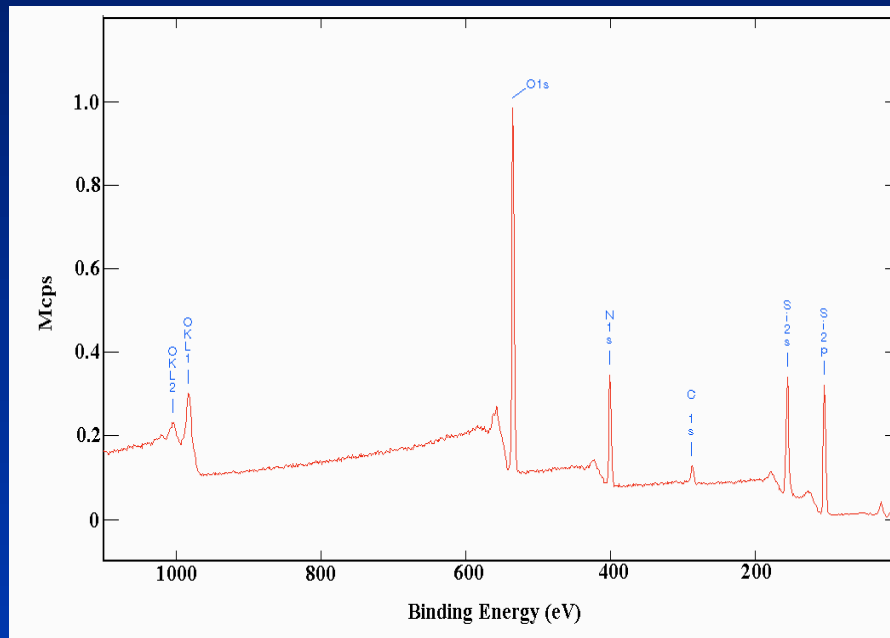
- The material to be analyzed is in UHV
- The surface is irradiated with photons in X-ray range (Alk α 1486.6 eV)
- The emitted e⁻ are separated according to their energy by the analyzer and counted



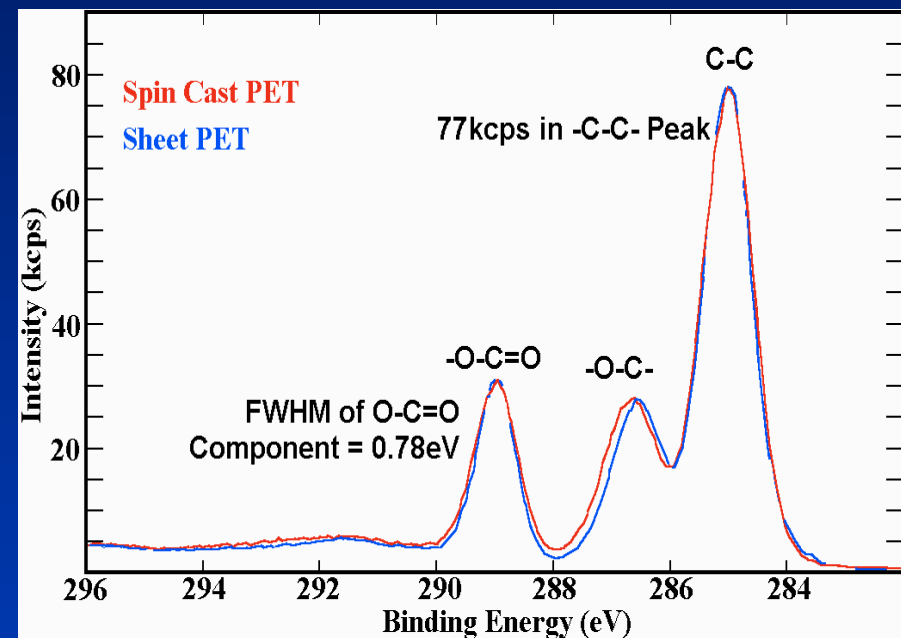
Courtesy of Thermo VG Scientific

X-ray Photoelectron Spectroscopy (XPS)

Type of information

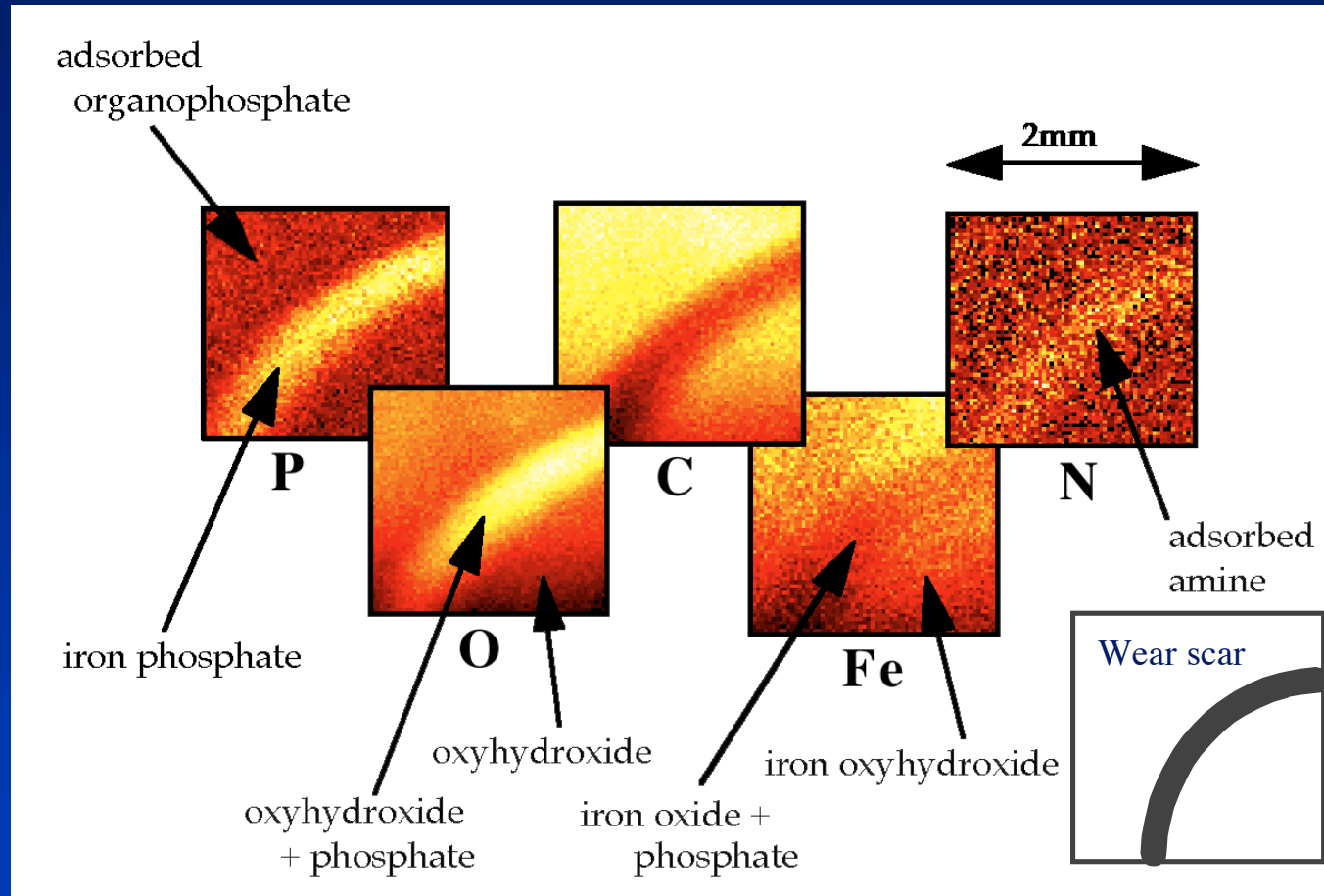


elemental identification



chemical state identification

Imaging XPS Study of Additive-Surface Interactions



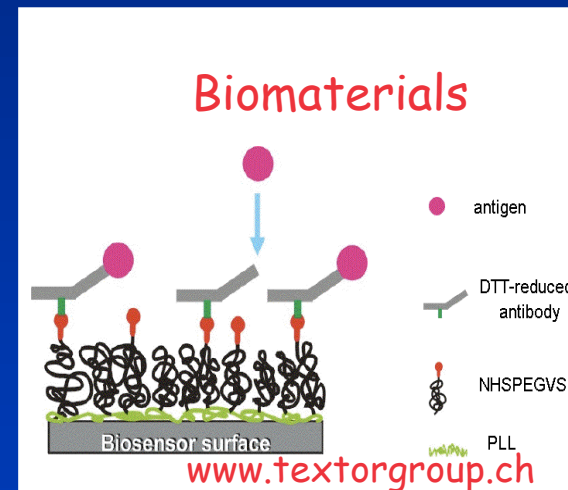
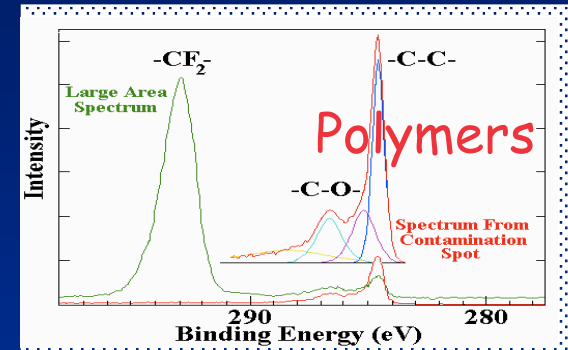
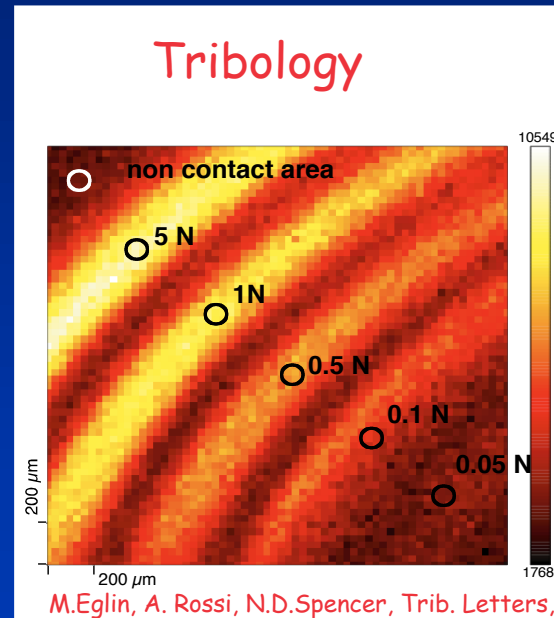
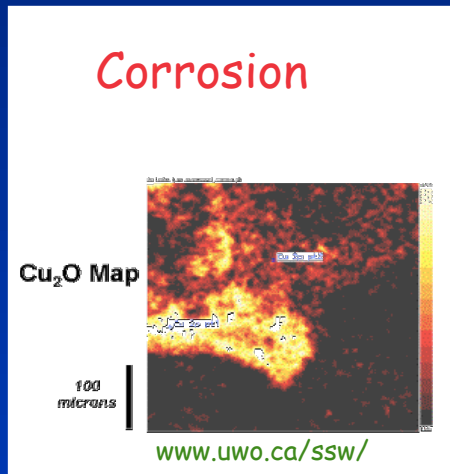
Irgalube® 349/PAO/100Cr6 following tribotesting

Quantitative analysis is mainly performed under the assumption of the homogeneity of a material.

Catalysis

Catalysis & Interfacial Chemistry Effort

$C_2H_4 + O \rightarrow C_2H_4O$
 $C_2H_4 + O \rightarrow CO_2 + H_2O$

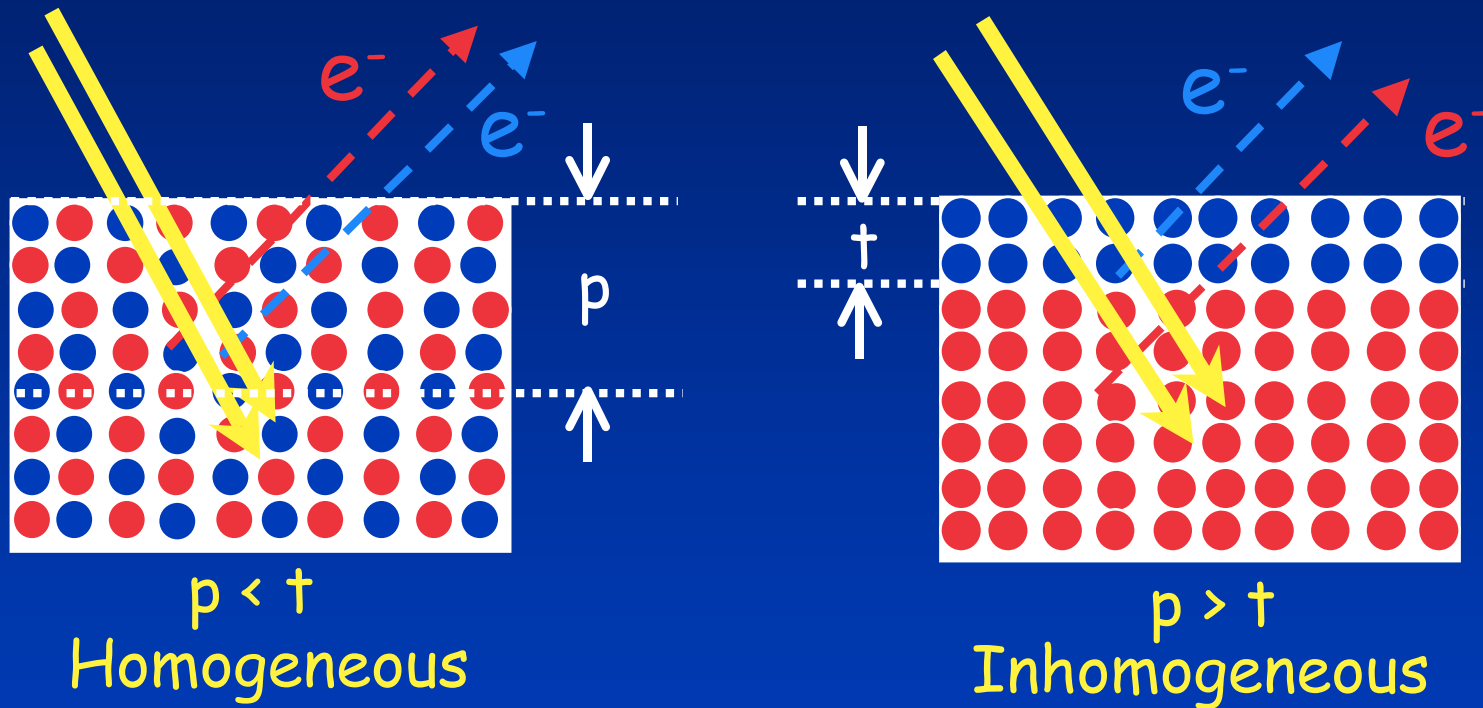


The need of the study of very thin films with a depth resolution on the nanometers range stimulates the proposal of new models for XPS quantification.

Outline

- The need for quantitative XPS information
- Real surfaces
- Modeling of real surfaces: the three layer model
- Examples
- Outlook

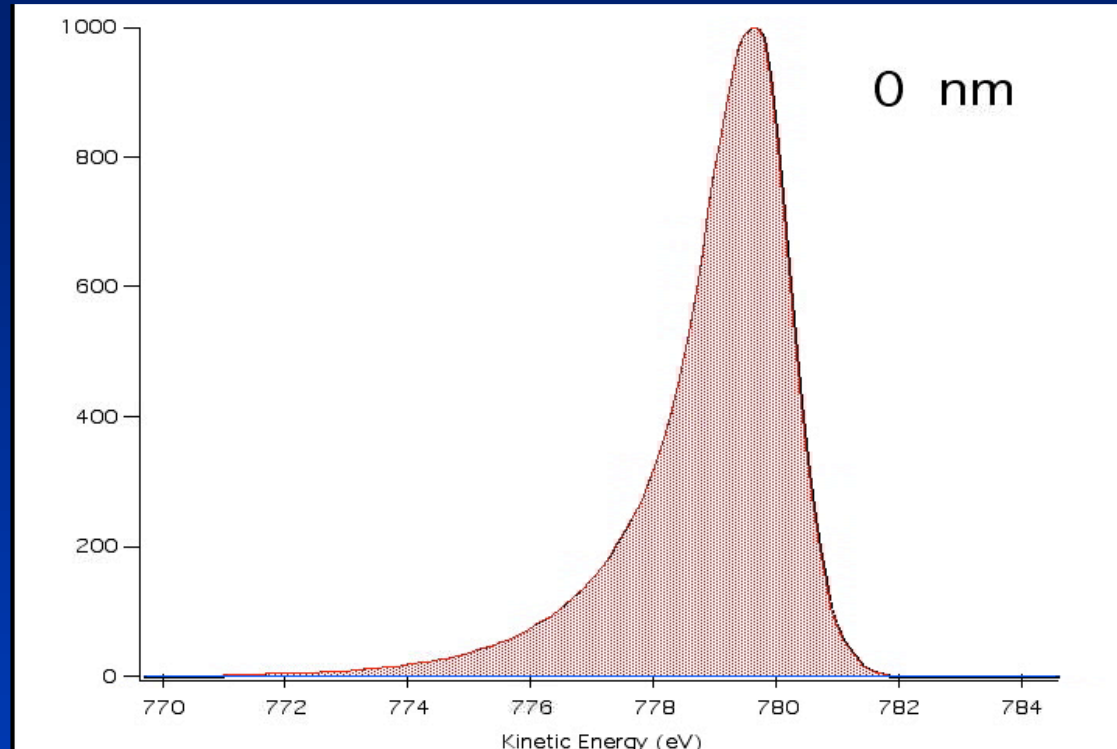
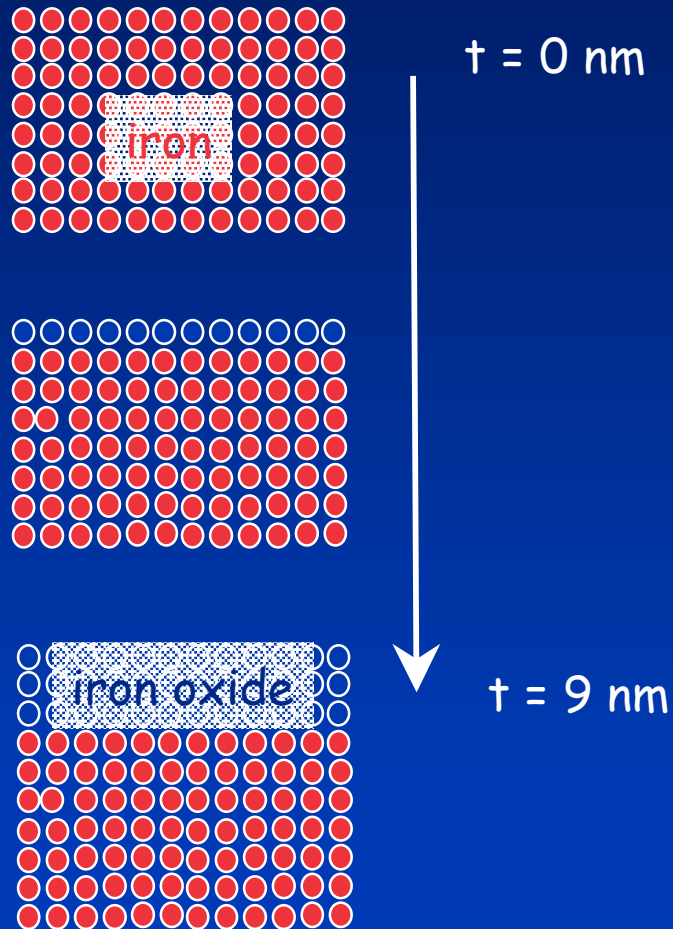
XPS depth resolution in the nanometer range



p sampling depth, t thickness of layer

Attenuation of XPS photoelectrons

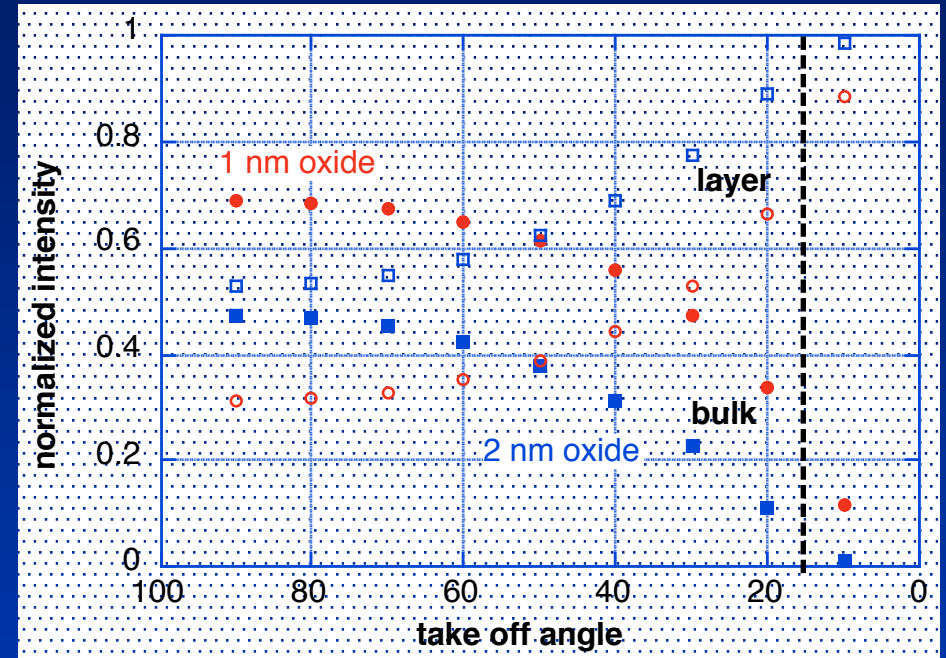
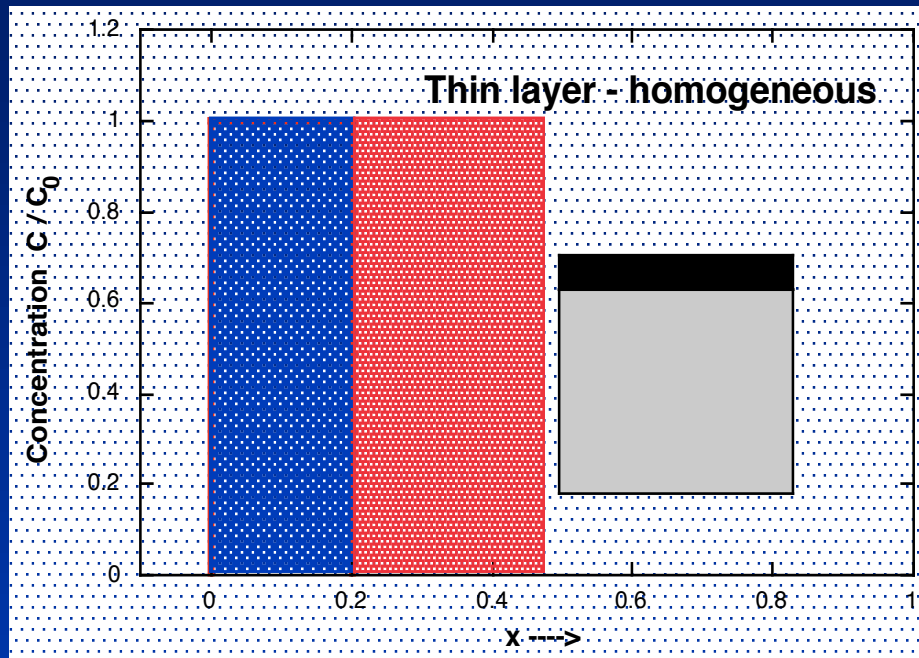
Example of an iron oxide layer on iron



Electrons from the bulk are attenuated by any layer on the surface

Modeling oxide layer - ARXPS

Example of an iron oxide layer on iron



$$I_{\text{bulk}} = I_{\text{bulk}}^0 \exp(-x_L / (\lambda_L \sin(\theta)))$$

$$I_{\text{Layer}} = I_L^\infty (1 - \exp(-x_L / (\lambda_L \sin(\theta))))$$

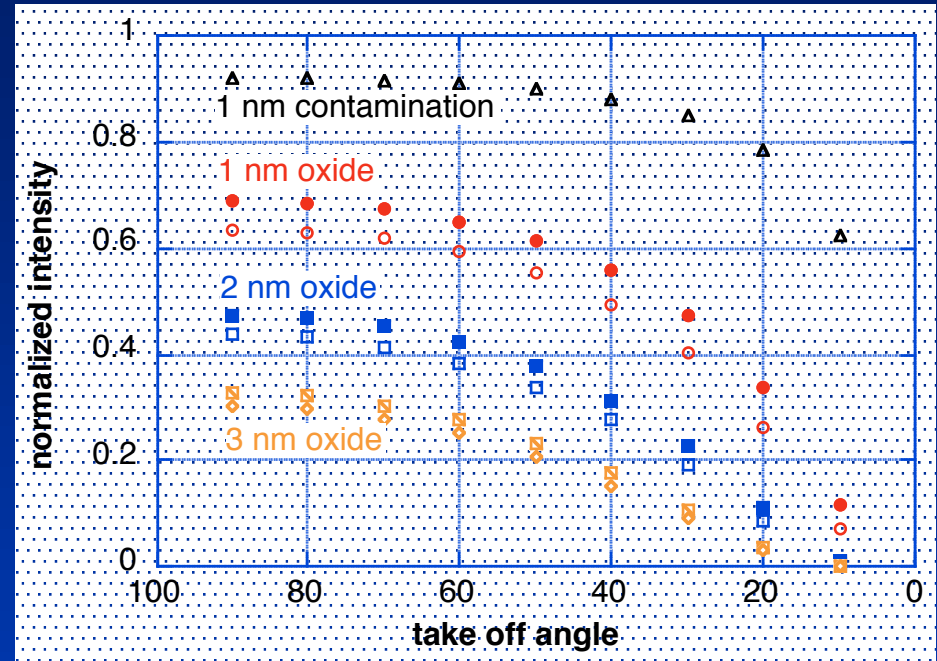
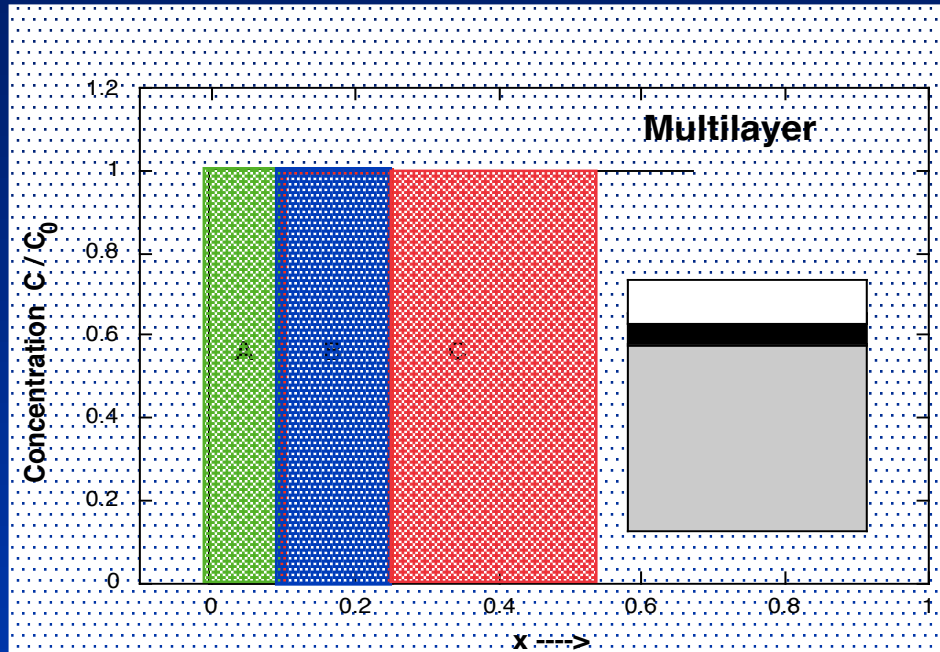
decreases with x_L and angle

increases with x_L and angle

Electrons from the bulk are progressively attenuated at lower take off angles.

Modeling contamination overlayer - ARXPS

Example of an iron oxide layer on iron with contamination



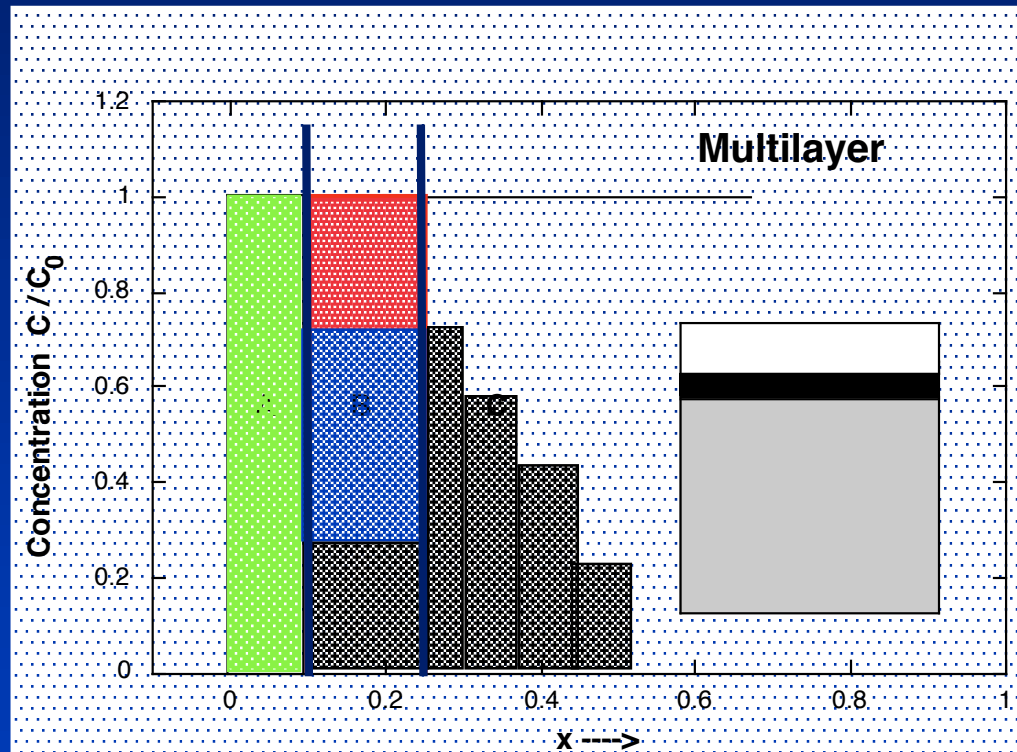
$$I_{\text{bulk}} = I_{\text{bulk}}^0 \exp(-x_L / (\lambda_L \sin(\theta))) * \exp(-x_C / (\lambda_L \sin(\theta)))$$

$$I_{\text{Layer}} = I_L^\infty (1 - \exp(-x_L / (\lambda_L \sin(\theta))) * \exp(-x_L / (\lambda_L \sin(\theta))))$$

Layer thickness x_L and x_C are corrected for density

Modeling of multicomponent real surfaces

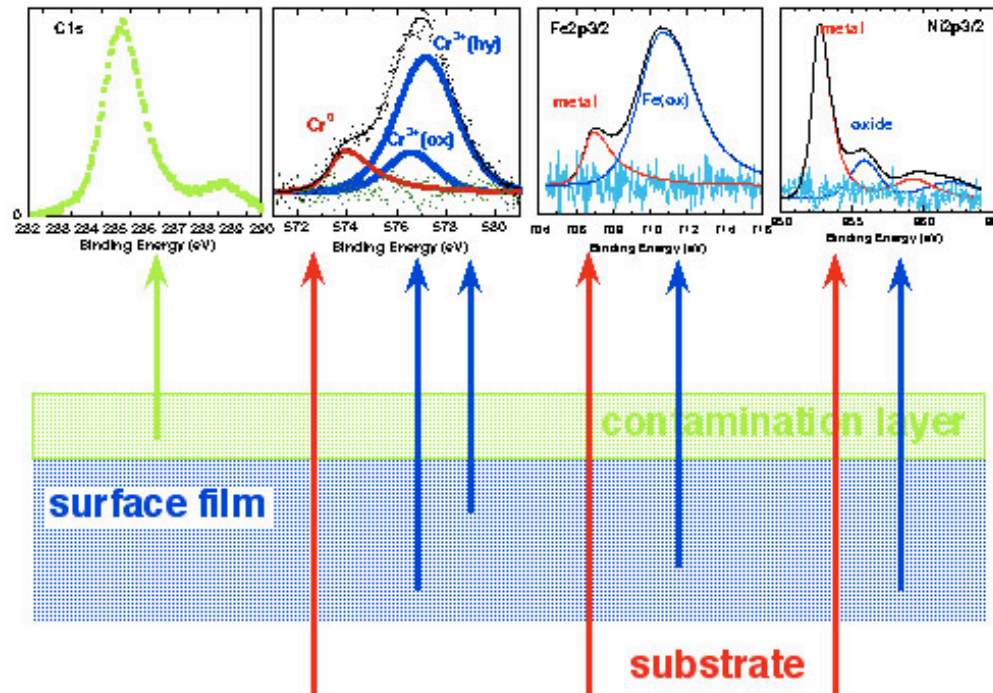
Real surfaces are multicomponent with unknown in-depth
Distribution and a contamination overlayer



- Electron attenuation
- Effect of layer density
- Gradients in composition
- Contamination overlayer

How to calculate composition and thickness from XPS data ?

Three layer model for real surfaces



Each layer is homogeneous in thickness,
composition and density
Electron attenuation

K. Asami, K. Hashimoto, *Corrosion Science*, 24, 83, 1984

A. Rossi and B. Elsener, *Surface and Interface Analysis*, 18, 1992, 499-504.

B. Elsener and A. Rossi, *Electrochimica Acta*, 37, 1992, 2269-2276

Three-layer model: the equations

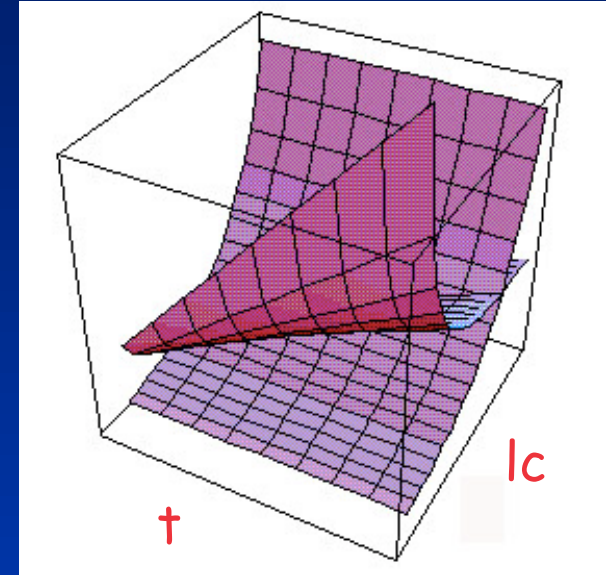
$$I_i^{ox} = \frac{[g_i^{ox} \quad c_i^{ox} \quad \rho_i^{ox} \quad \rho_i^{ox}]}{A_i} * \exp\left(\frac{t}{\rho_i^{ox}}\right) * \exp\left(\frac{V_c}{c_i^c}\right)$$

$$I_i^{sub} = \frac{[g_i^{sub} \quad c_i^{sub} \quad \rho_i^{sub} \quad \rho_i^{sub}]}{A_i} * \exp\left(\frac{t}{\rho_i^{ox}}\right) * \exp\left(\frac{V_c}{c_i^c}\right)$$

Three-layer model: parametric equations

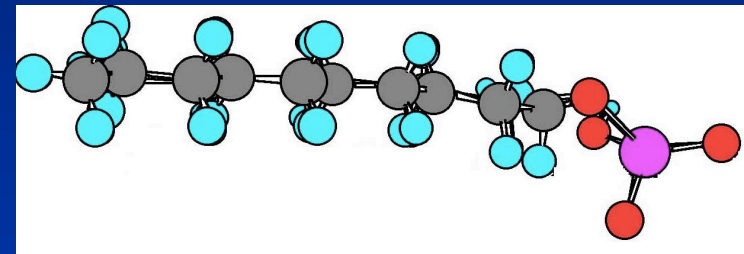
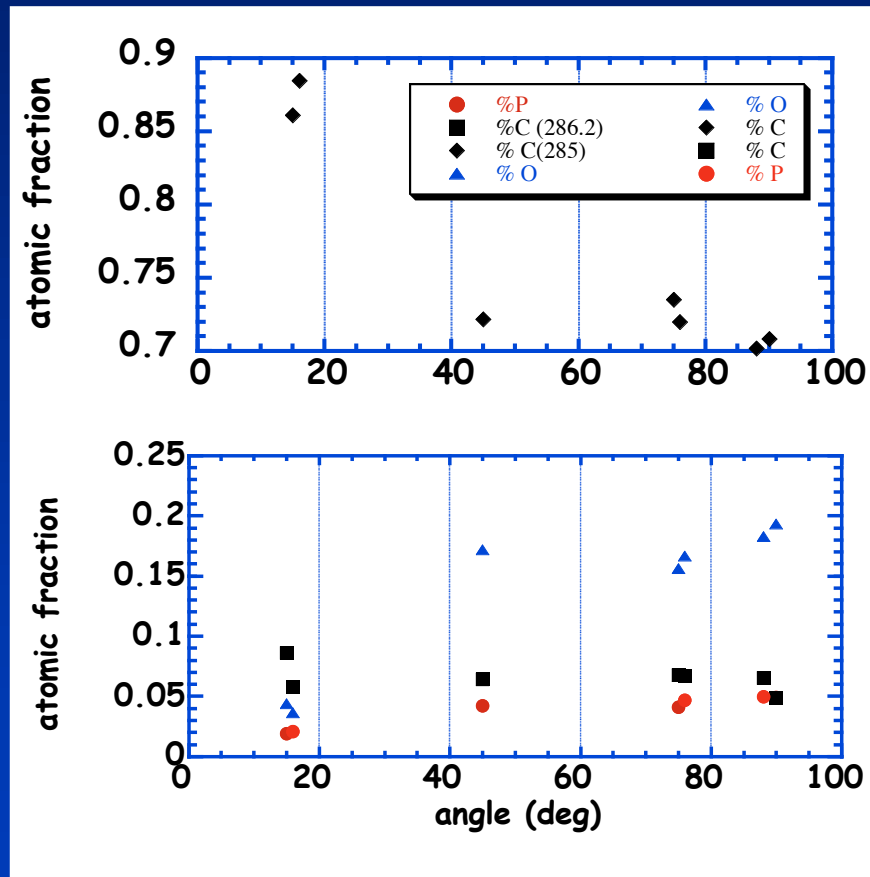
$$f_1(t, l_c) = \sum_{i=1}^n \frac{I_i^{sub} k_i^{sub}}{\tau_i^{ox}} \exp\left(-\frac{t}{\tau_i^{ox}}\right) * \exp\left(-\frac{l_c}{\lambda_i^c}\right) \rho_i^{ox}$$

$$f_2(t, l_c) = \frac{I_c K_c \rho_c^{ox}}{\exp\left(-\frac{l_c}{\lambda_c^c}\right)} \rho_c^{ox}$$



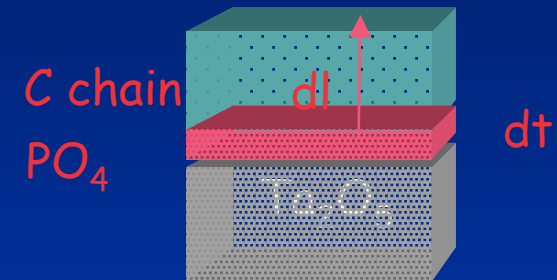
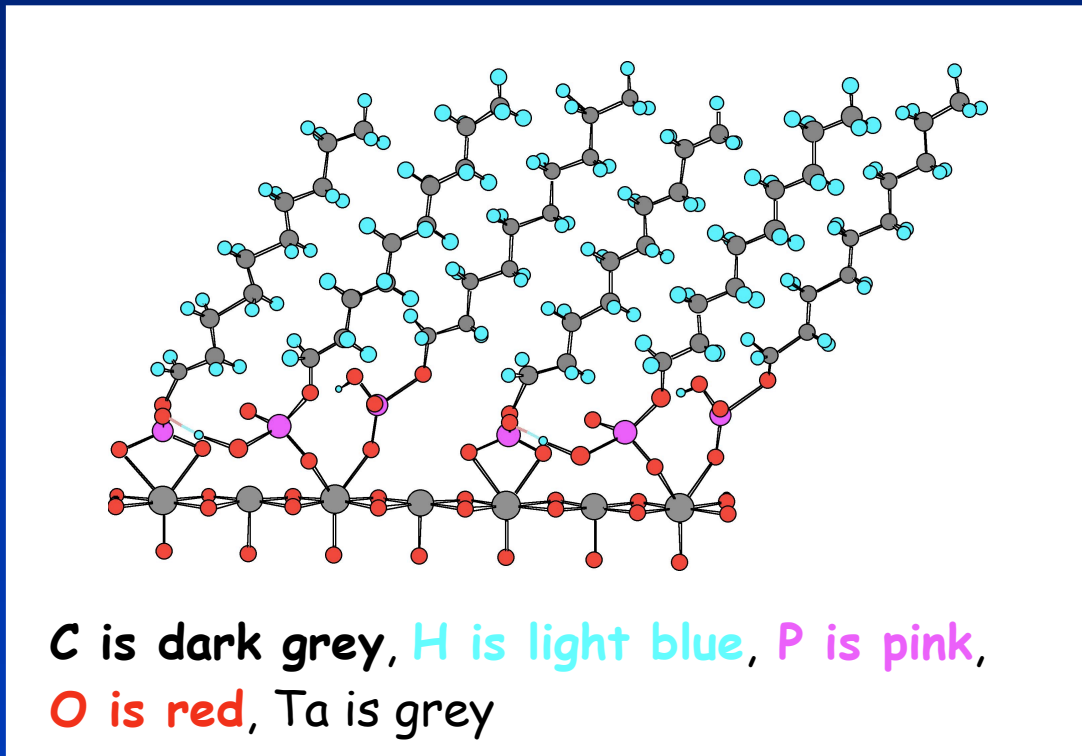
Numerical methods based on versions of Newton's method are used to find numerical approximations to the solutions of the equations. The composition of each layer are calculated simultaneously.

Self-Assembled Monolayers ODP on Ta₂O₅ ARXPS



Phosphate head is
at the interface

Self-Assembled Monolayers ODP on Ta_2O_5



layer homogeneity
e- attenuation according
to Lambert-Beer law
no gradients

Self-Assembled Monolayers

ODP on Ta₂O₅

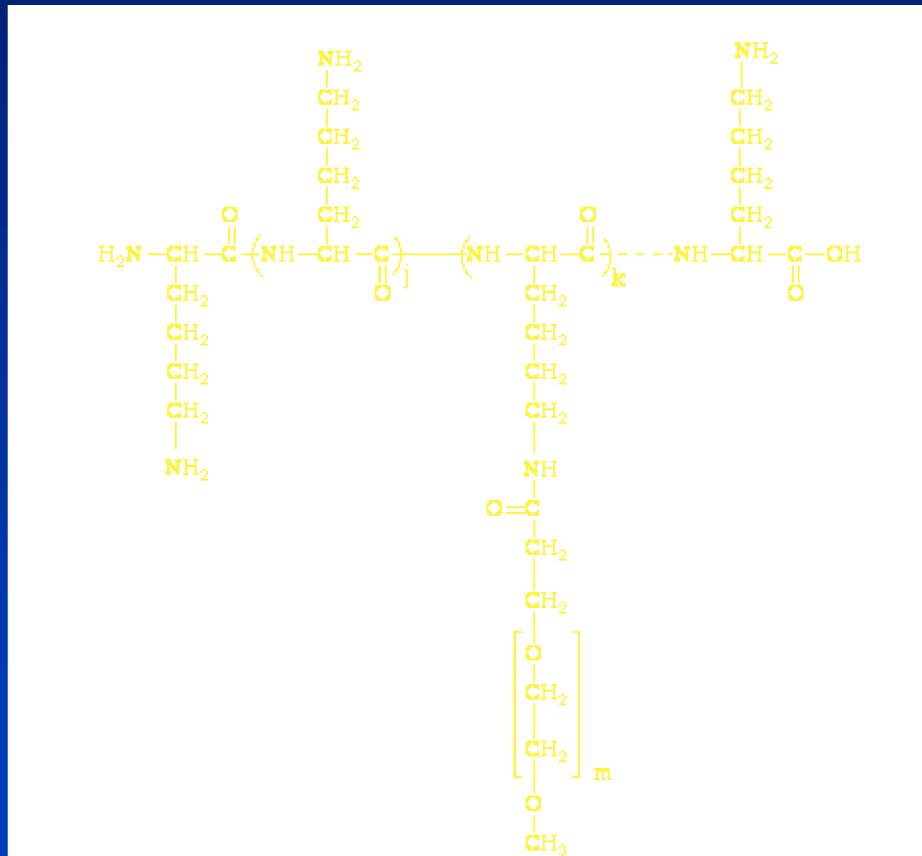
Thickness and composition of self-assembled ODP monolayer on Ta₂O₅ *.

	C	O	P	O	Ta
	ODP chain	polar head		substrate Ta ₂ O ₅	
thickness (nm)	l _c = 1.2±0.2	t = 1.2±0.1 ₅		semi infinite	
composition weight%					
theoretical	-	67.4	32.6	18.1	81.9
experimental	-	69±1	31±1	17.3±1	82.7±1

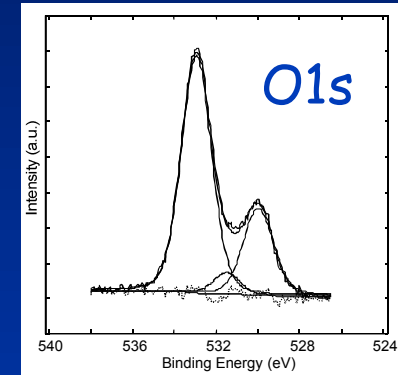
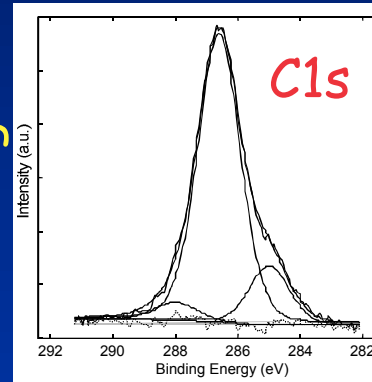


Protein resistant biomaterials

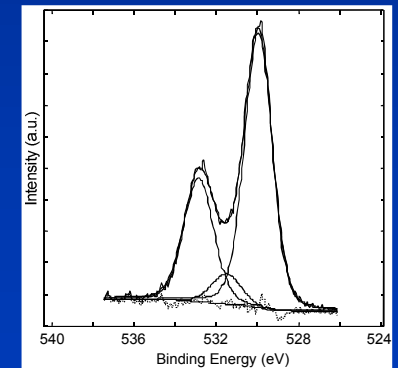
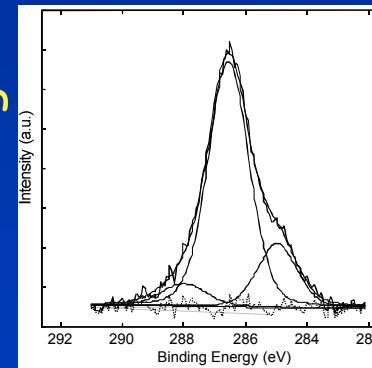
PLL-g-PEG on Nb₂O₅



15 deg



75 deg



Protein resistant biomaterials

PLL-g-PEG on Nb₂O₅

angle	thickness (nm)		composition interface (PLL)			composition bulk	
	PEG	PLL	C1s	N1s	O1s	metal	O1s
Exper.	1.1±0.3	0.6±0.2	59	21	20	72	28
Calc.	-	-	59	23	18	70	30

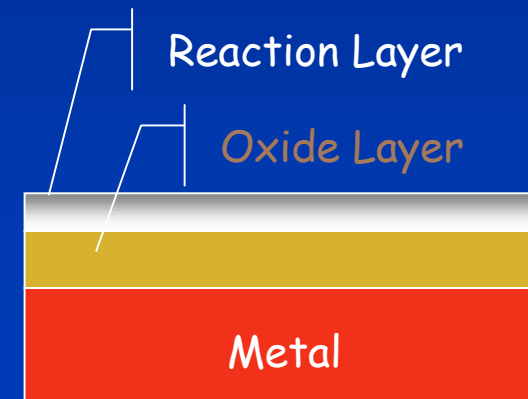
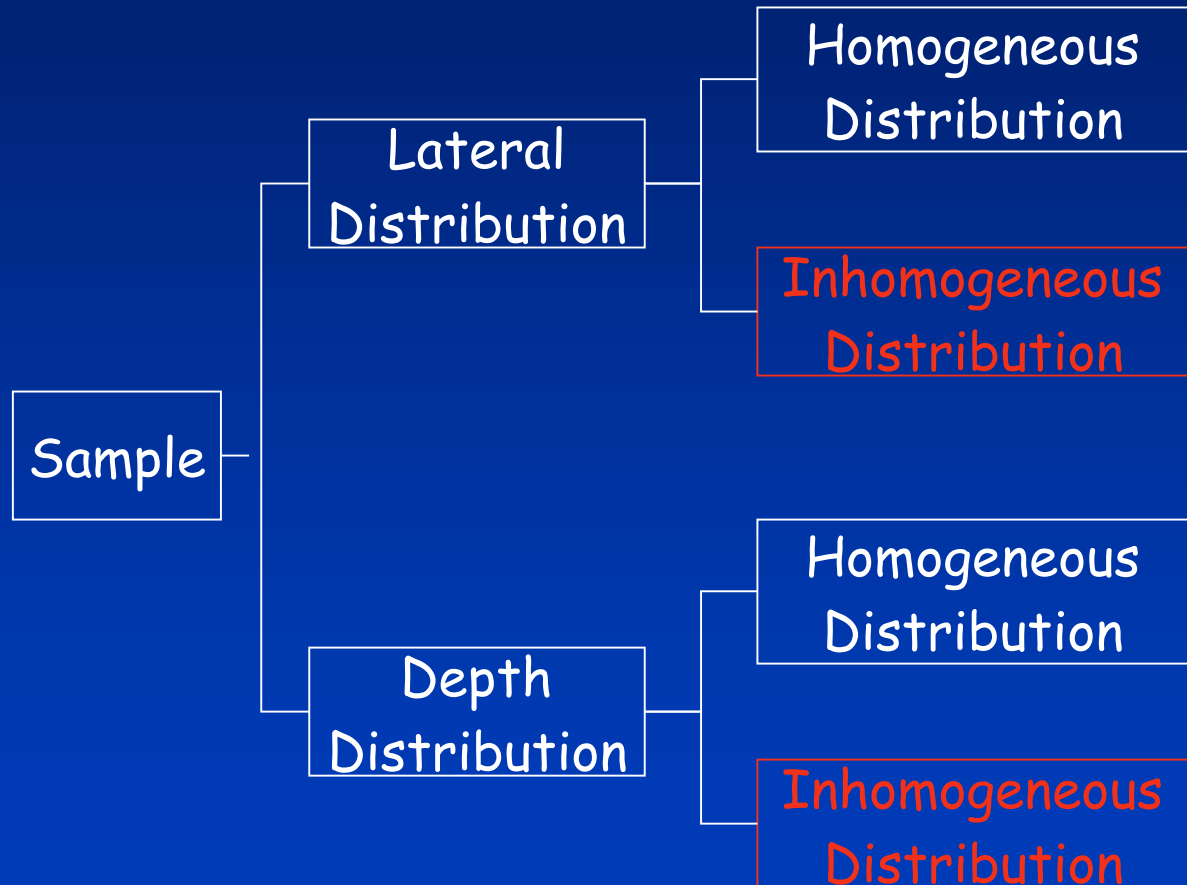
$$\square \text{ PEG} = 2 \text{ g cm}^{-3}$$

$$\square \text{ PLL} = 1 \text{ g cm}^{-3}$$

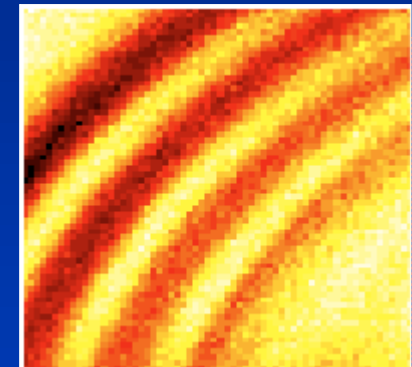
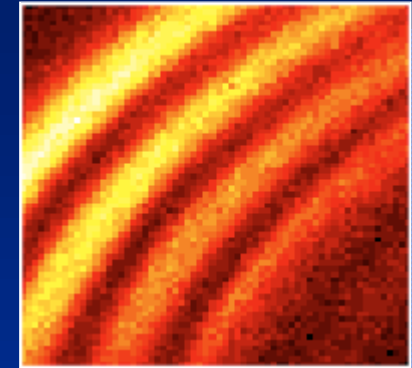
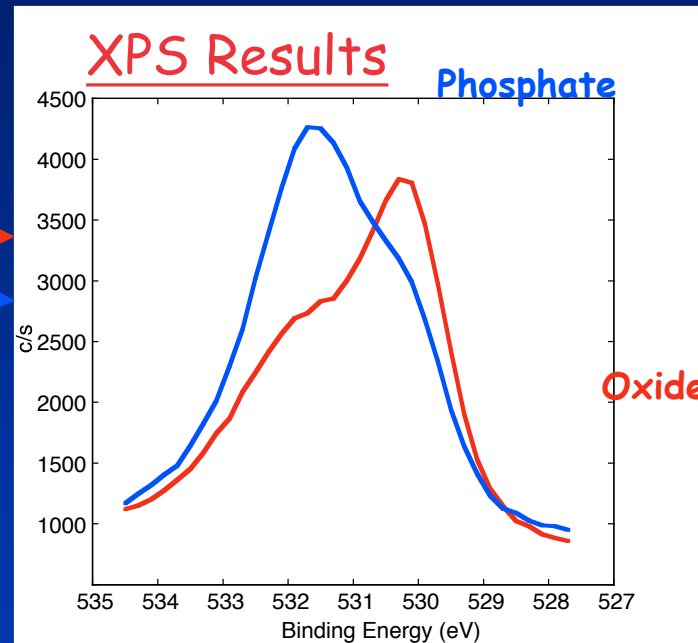
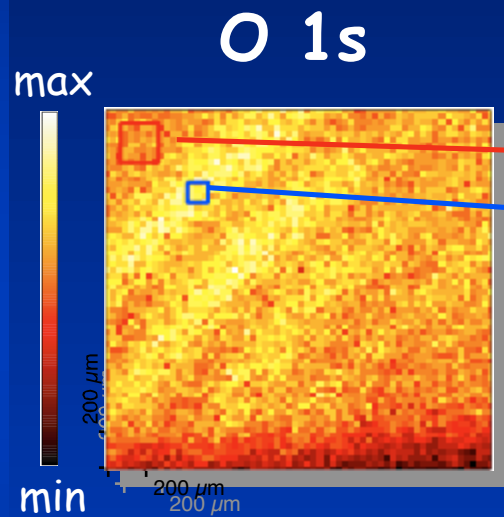
$$\square \text{ Nb}_2\text{O}_5 = 4.47 \text{ g cm}^{-3}$$

The thicknesses are fully consistent with monolayer coverage of PLL-g-PEG and with a surface coverage of 148 ng cm⁻³ measured by OWLS.

Real surfaces



Imaging XPS

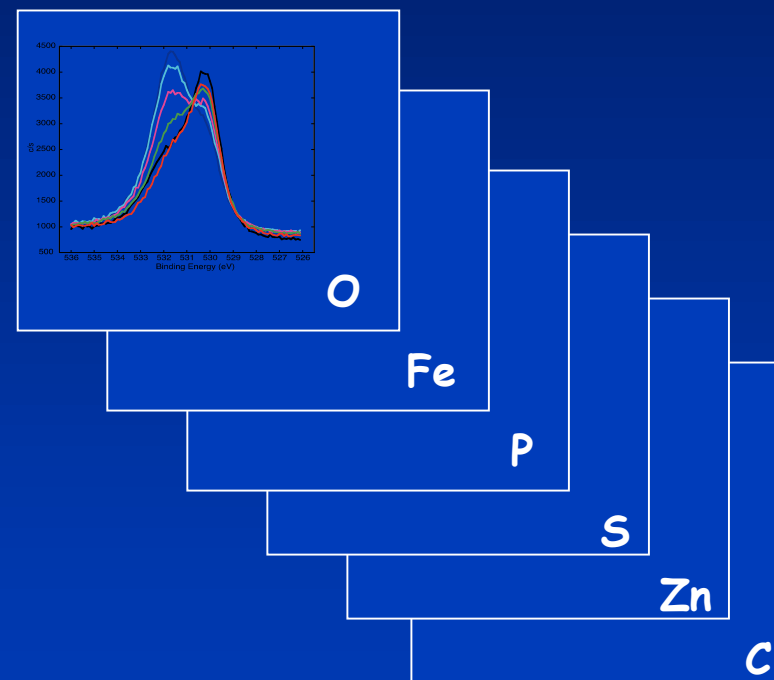
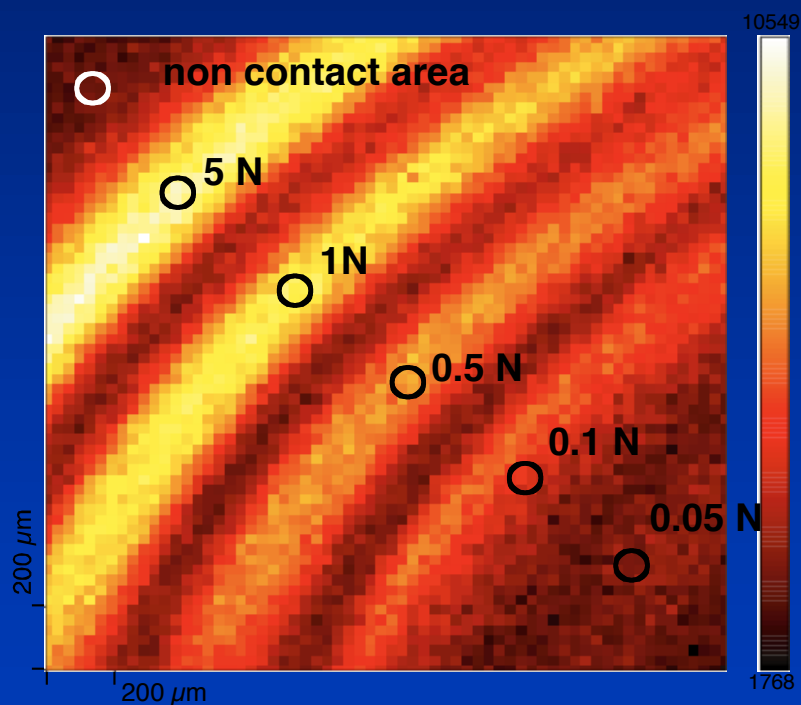


Extract Spectra

Reconstruct
Map

From Imaging to Spectroscopy

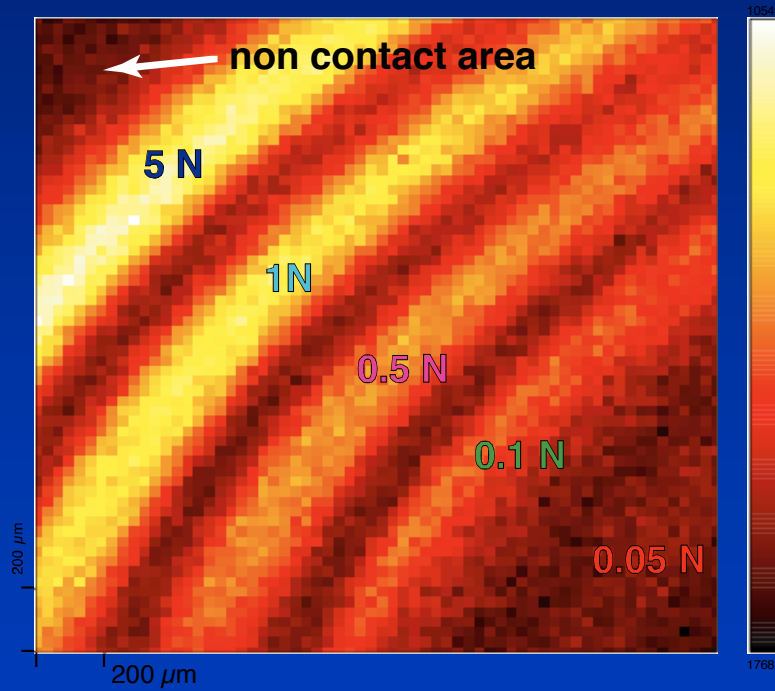
O 1s



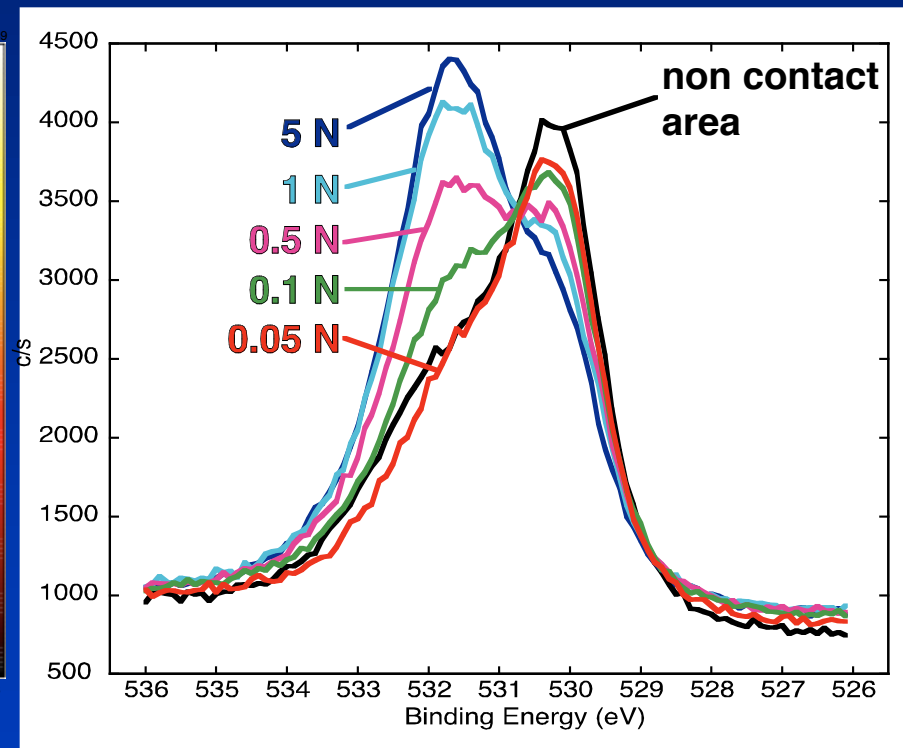
Select Areas for High Resolution-Small Area XPS

XPS Results

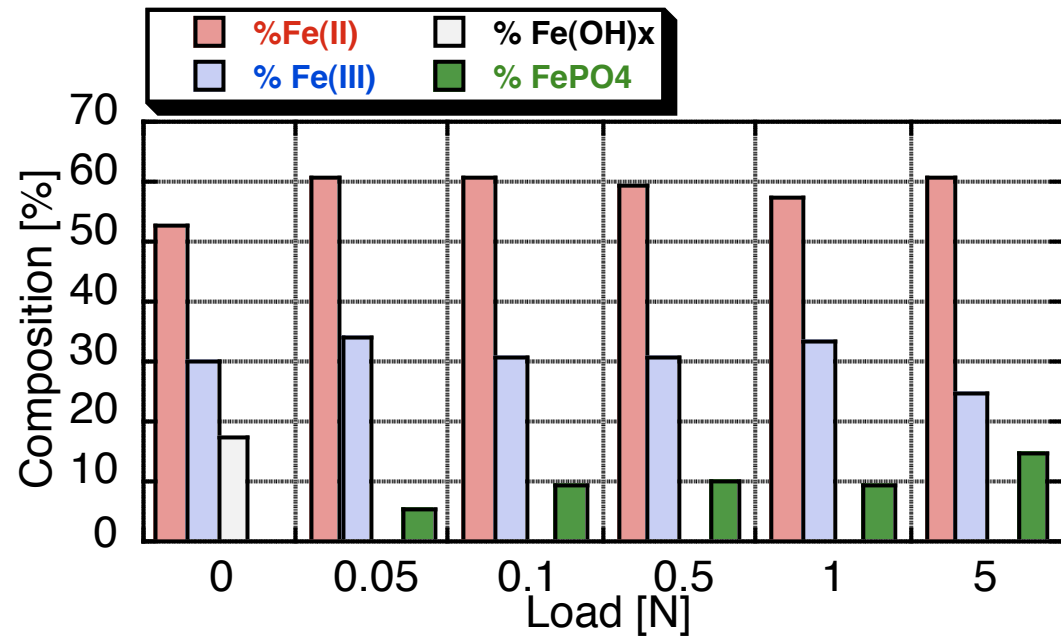
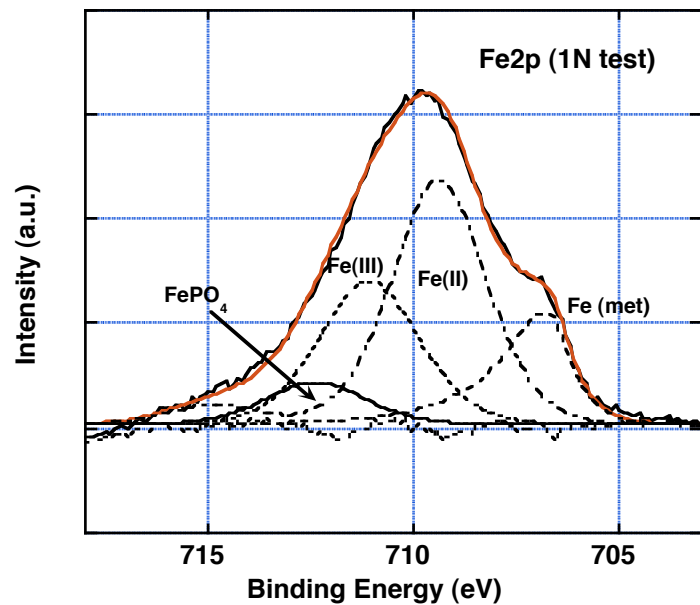
O 1s



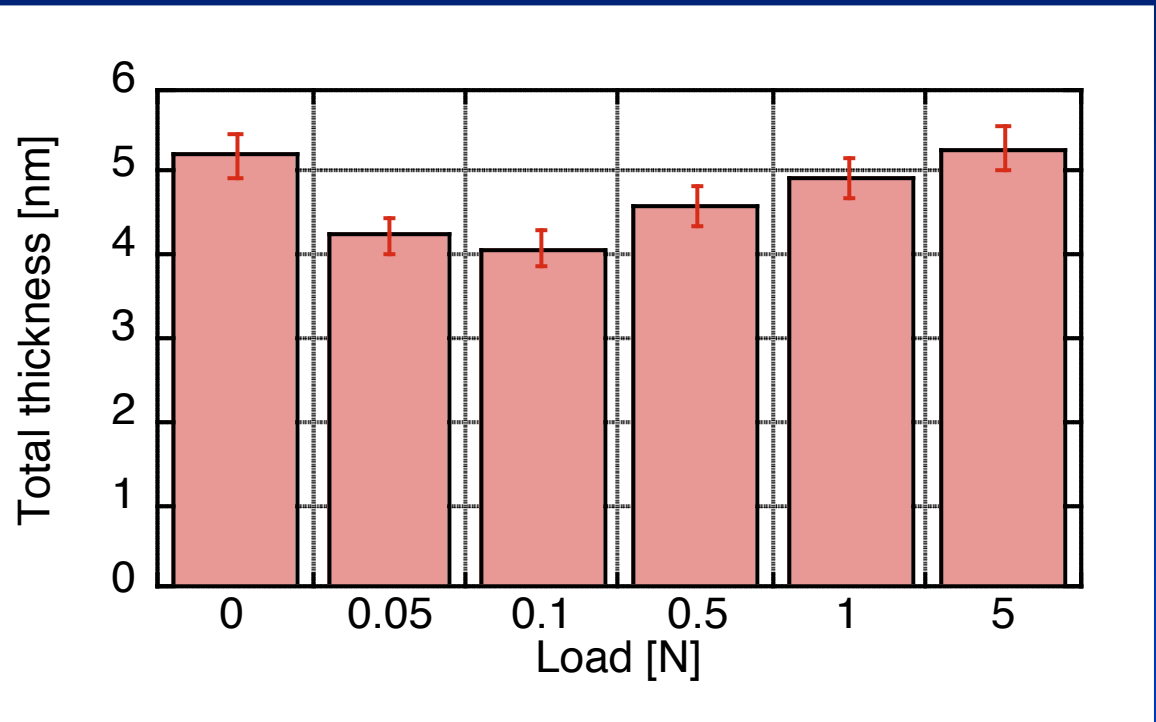
O 1s



XPS Results (Iron)



XPS Results - film thickness



Outlook

The newest spectrometers allow imaging quantification with:
higher lateral resolution ($<3\mu\text{m}$)
collection of spectroscopic data with high sensitivity

The application of the **three-layer model** at any point of the image will provide information:

- local thicknesses variations
- local layer composition changes
- local interface composition variations

Acknowledgments

Marco Ferraris, Domenico De Filippo, Bernhard Elsener, Nic Spencer, Marcus Textor

Michael Eglin, Ning-Ping Huang, Laurence Ruiz